



*1752*  
PATENT

SHR 7.045APC

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Masuda et al.  
Appl. No. : 10/568,126  
Filed : February 14, 2006  
For : POSITIVE PHOTORESIST  
COMPOSITION AND RESIST  
PATTERN FORMATION  
Examiner : Chu, John S. Y.  
Group Art Unit : 1752

CERTIFICATE OF MAILING

I hereby certify that this correspondence and all marked attachments are being deposited with the United States Postal Service as first-class mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450, on

October 30, 2006

(Date)

*Daniel Altman*

Daniel E. Altman, Reg. No. 34,115

AMENDMENT AND RESPONSE TO OFFICE ACTION

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

In response to the Office Action mailed **June 28, 2006**, Applicants respectfully request the Examiner to enter the following amendments and consider the following remarks.

A one-month extension of time is necessary for consideration of this Amendment. Please charge the \$120 fee for this one-month extension, as well as any other required fees, including any additional fees for extensions of time, to **Deposit Account No. 11-1410**.

**Amendments to the claims** are reflected in the **listing of claims** which begins on page 2 of this paper.

**Remarks** begin on page 3 of this paper.

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